What is claimed is:

1 1.	A method	of making an	electrical	structure	, comprising
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- 2 preparing a database;
- placing a substrate in a first laser processing system, the substrate
- 4 comprising an electrically insulating material and a first blanket layer of conductive
- 5 material disposed on a first surface thereof;
- forming at least one fiducial by laser etching;
- 7 removing portions of the conductive material by laser etching so as to form
- 8 isolated conductive traces;
- laser etching at least one alignment hole suitable for receiving therethrough at
- 10 least one alignment pin;
- 11 laser etching at least one folding line; and
- singulating the electrical structure;
- wherein forming the at least one fiducial, removing portions of the conductive
- material; etching the at least one alignment hole; etching at least one folding line;
- and singulating the electrical structure are all performed within the first laser
- 16 processing system.
- 1 2. The method of Claim 1, wherein forming the at least one fiducial, removing
- 2 portions of the conductive material; cutting the at least one alignment hole; cutting at
- 3 least one folding line; and singulating the electrical structure are all performed within

- 4 the first laser processing system without removing the substrate from the laser
- 5 processing system until the singulation operation is complete.
- 1 3. The method of Claim 1, wherein the conductive material comprises copper.
- 1 4. The method of Claim 1, wherein forming at least one fiducial comprises
- 2 removing portions of the conductive material.
- 1 5. The method of Claim 4, wherein forming at least one fiducial further
- 2 comprises removing portions of the substrate.
- 1 6. The method of Claim 1, wherein the database is communicatively coupled to
- 2 the laser processing system so as to provide control signals that direct at least a
- 3 portion of a plurality of operations of the laser processing system to the laser
- 4 processing system.
- 1 7. The method of Claim 5, wherein the electrical structure is a space
- 2 transformer.
- 1 8. The method of Claim 5, wherein the substrate comprises a material selected
- 2 from the group consisting of FR-4, epoxy, and polyimide.

- 1 9. The method of Claim 5, wherein the substrate comprises a board suitable as
- 2 a printed circuit board.
- 1 10. The method of Claim 5, wherein the substrate comprises a flexible material
- 2 suitable for flex circuits.
- 1 11. The method of Claim 6, wherein a second layer of conductive material is
- 2 disposed on a second surface of the substrate.
- 1 12. The method of Claim 6, wherein the substrate comprises at least one
- 2 conductive trace formed therein.
- 1 13. The method of Claim 6, wherein the singulated electrical structure is a single-
- 2 chip package.
- 1 14. The method of Claim 6, wherein the singulated electrical structure is a multi-
- 2 chip package.
- 1 15. The method of Claim 3, further comprising removing a portion of a passivation
- 2 layer disposed the copper, wherein the copper underlying the removed portion of the
- 3 passivation layer remains substantially unremoved.

- 1 16. A method of making an electrical structure, comprising:
- 2 providing an insulating substrate having a first major surface and a second
- 3 major surface opposite the first major surface, with a layer of metal disposed on the
- 4 first major surface; and
- removing, by laser etching, at least one portion of the layer of metal so as to
- 6 form at least one trace and at least one space adjacent thereto;
- 7 wherein the at least one trace has a height, a width, and a first aspect ratio
- 8 (height/width); and the at least one space has a height, a width, and a second
- 9 aspect ratio (height/width), and wherein the second aspect ratio is greater than the
- 10 first aspect ratio.
 - 1 17. The method of Claim 16, wherein the trace comprises copper, and the height
 - 2 of the conductive trace is in the range of 9 to 72 microns.
 - 1 18. The method of Claim 17, wherein the second aspect ratio is in the range of
 - 2 0.75 to 50.
 - 1 19. The method of Claim 18, wherein the laser etching is performed in a first laser
- 2 etching system, further comprising forming at least one fiducial, and at least one
- 3 alignment hole, without removing the substrate from the first laser etching system,
- 4 and without realigning the substrate within the first laser etching system.

- 1 20. The method of Claim 19, further comprising forming at least one bar code,
- 2 without removing the substrate from the first laser etching system, and without
- 3 realigning the substrate within the first laser etching system.
- 1 21. The method of Claim 20, further comprising forming at least one folding line,
- 2 without removing the substrate from the first laser etching system, and without
- 3 realigning the substrate within the first laser etching system.
- 1 22. The method of Claim 19, further comprising forming at least one passivation
- 2 opening.
- 1 23. A method of forming a space transformer, comprising:
- 2 placing a substrate with a first major surface and a second major surface, the
- 3 substrate comprising an electrically insulating material, and a first layer of material
- 4 disposed on the first major surface, into a first pulsed laser etching system;
- 5 etching, with the first pulsed laser etching system, portions of the first layer
- and portions of the substrate to form at least one fiducial;
- without removing the substrate from the first pulsed laser etching system,
- 8 etching portions of the first layer to form conductive traces separated by spaces;
- 9 without removing the substrate from the first pulsed laser etching system,
- 10 etching portions of the first layer and the substrate to form alignment holes;

11	without removing the substrate from the first pulsed laser etching system,
12	laser etching folding lines; and
13	without removing the substrate from the first pulsed laser etching system,
14	etching portions to singulate the space transformer;

- wherein the width of the spaces is less than the width of the conductive traces.
- 1 24. The method of Claim 23, further comprising the first laser etching system
- 2 receiving control information from a database, wherein the control information directs
- 3 at least a portion of the etching by the first pulsed laser etching system with respect
- 4 to the coordinates of a material to be etched.
- 1 25. The method of Claim 24, wherein the coordinates of the material to be etched
- 2 are selected from a single coordinate system, independent of the feature formed by
- 3 the etching.
- 1 26. The method of Claim 23, wherein etching comprises:
- exposing a first portion of the first material to a first laser pulse, the first
- 3 portion determined by a first set of coordinates of a first coordinate system;
- exposing a second portion of the first material to a second laser pulse, the
- 5 second portion determined by a second set of coordinates of the first coordinate
- 6 system; and

- exposing a third portion of the first material to a third laser pulse, the third portion determined by the first set of coordinates of the first coordinate system.
- 1 27. The method of Claim 23, wherein exposing the first portion to the third laser
- 2 pulse occurs subsequent to exposing the second portion to the second laser pulse.
- 1 28. The method of Claim 23, wherein exposing the first portion to the third laser
- 2 pulse occurs prior to exposing the second portion to the second laser pulse.
- 1 29. The method of Claim 23, wherein etching comprises:
- 2 exposing a first coordinate position of the first material to a first laser pulse;
- exposing a second coordinate position of the first material to a second laser
- 4 pulse; and
- 5 exposing at least a portion of a third coordinate position of the first material to
- 6 a third laser pulse.
- 1 30. The method of 29, wherein exposing the at least a portion of the first
- 2 coordinate position of the first material to the third laser pulse occurs subsequent to
- 3 exposing the second coordinate position of the first material to the second laser
- 4 pulse.

- 1 31. The method of Claim 29, wherein exposing the at least a portion of the first
- 2 coordinate position of the first material to the third laser pulse occurs prior to
- 3 exposing the second coordinate position of the first material to the second laser
- 4 pulse.
- 1 32. The method of Claim 25, further comprising forming, by laser etching, at least
- 2 one graphical symbol from the first layer of material.
- 1 33. The method of Claim 31, wherein the at least one graphical symbol is a bar
- 2 code.
- 1 34. The method of Claim 25, further comprising removing at least one portion of
- 2 an adhesive layer, the adhesive layer disposed between the first material and the
- 3 substrate, the at least one portion corresponding to a region defined by an overlying
- 4 space, wherein removing the at least one portion of the adhesive layer is performed
- 5 without removing the substrate from the first laser etching system, and without
- 6 realignment of the substrate.